

SilcoNert® 2000

Providing the ultimate inert coating technology. Also known as Sulfinert® and Siltek®

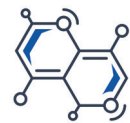
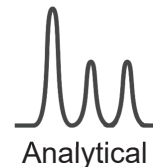
Overview

The SilcoNert® 2000 coating process results in a chemically protective barrier of amorphous silicon that is further functionalized to provide the most inert surface available (patent info at www.silcotek.com/IP). Applied via chemical vapor deposition (CVD), the SilcoNert® 2000 process is ideal when trace-level testing accuracy (< parts-per-million) of sulfurs, mercury, ammonia, or other active compounds is imperative.



Key Applications and Benefits

- Non line-of-sight process; all holes and complex geometries will be coated
- Eliminate adsorption and retesting
- Obtain faster calibrations
- Gain full confidence in your analytical results



SilcoNert® 2000 Specifications

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| Coating Structure: | Functionalized hydrogenated amorphous silicon |
| Deposition Process: | Thermal chemical vapor deposition (not plasma-enhanced) |
| Maximum Temperature*: | 450° C (inert atmosphere) 400° C (oxidative) |
| Substrate: | Compatibility: Stainless steel, exotic alloys, ceramics Size: Up to 78" (198 cm) Geometry: Any shape, including complex geometrics |
| Typical Thickness: | 100 - 500 nm |
| Hydrophobicity (contact angle): | ≥ 65° |
| Allowable pH Exposure: | 0 - 8 |